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## Correction: Broadening spectral responses and achieving environmental stability in SnS<sub>2</sub>/Ag-NPs/HfO<sub>2</sub> flexible phototransistors

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Correction for 'Broadening spectral responses and achieving environmental stability in SnS<sub>2</sub>/Ag-NPs/HfO<sub>2</sub> flexible phototransistors' by Muhammad Farooq Khan *et al.*, *Nanoscale*, 2024, **16**, 3622–3630, <https://doi.org/10.1039/D3NR04626E>.

The authors regret the use of the word nanoparticle or NP. The correct term is nanodot. Each instance of the term nanoparticle or NP should be read as nanodot. An expert has reviewed the usage and agreed that nanodot is the appropriate term.

The authors regret the omission of the Ag nanodot fabrication method in the original paper. An expert has reviewed the fabrication method and agreed it is consistent with the results presented.

The authors would also like to clarify why there are repetitive patterns in the SEM image in the Fig. 2a inset, of the original paper. The authors used AutoCAD software to design the nanodots on the SnS<sub>2</sub> flake. They were patterned with electron beam lithography and the silver was deposited with a thermal evaporator. Nanodots of approximately 50 nm, 100 nm and 150 nm were patterned.

The following details the Ag nanodots fabrication on the SnS<sub>2</sub> flake.

1. First, AutoCAD software was used to design patterns for Ag nanodots, as shown here in Fig. 1a. The appearance of repetitive patterns of nanodots observed in the SEM image is due to the intentional design followed.
2. The mechanically exfoliated SnS<sub>2</sub> flake was coated with an electron beam resist, *i.e.*, polymethyl methacrylate (PMMA).
3. The chips were baked at 170 °C for 2 minutes on a hot plate in the ambient environment.
3. Electron beam lithography was utilized to create the patterns of nanodots.
4. A ~15 nm thick layer of Ag metal was deposited using a thermal evaporator in a vacuum chamber.
5. The flakes were rinsed with acetone and methanol to remove the excessive Ag metal and complete the lift-off process, resulting in Fig. 1b and c shown here.

Additional examples to show the reproducibility of the process are shown here in Fig. 2.

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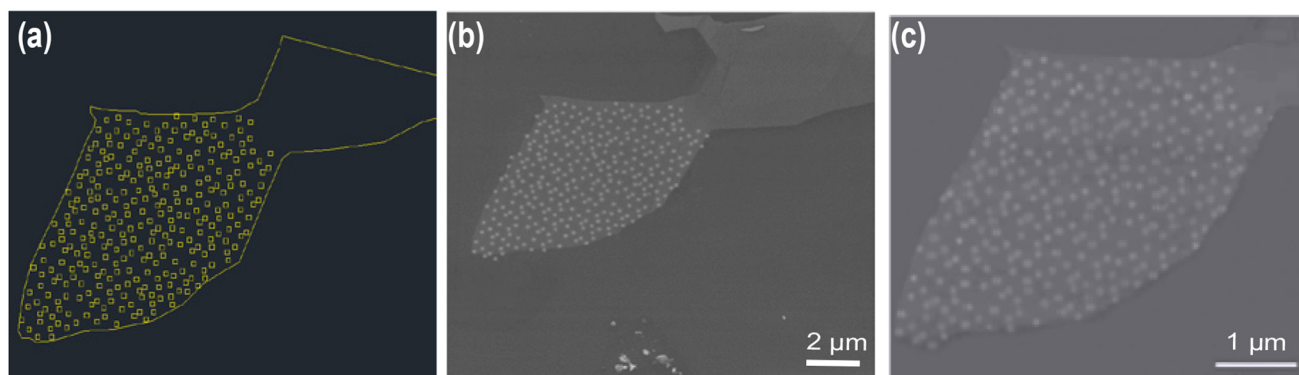


Fig. 1 (a) AutoCAD design pattern used to fabricate the Ag dots. (b) and (c) are SEM images of the Fig. 2a inset of the original paper.

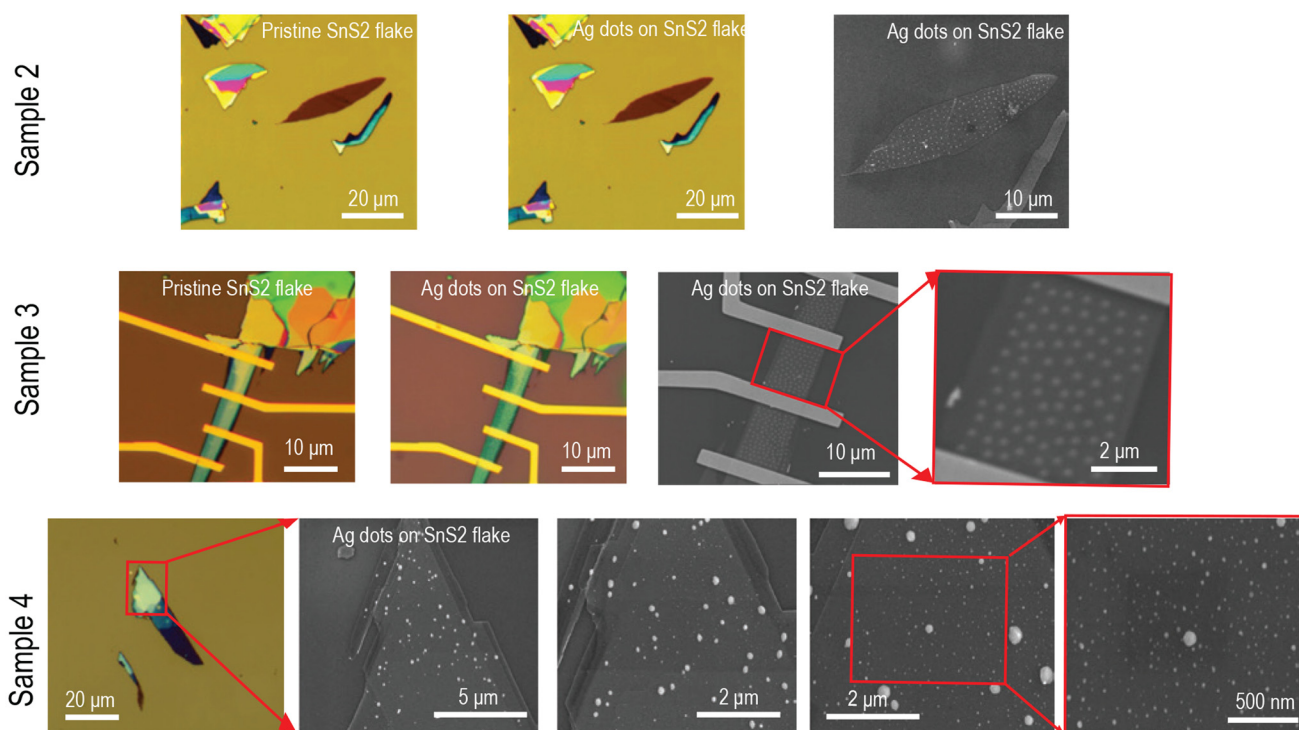


Fig. 2 Optical micrographs and SEM images of three other  $\text{SnS}_2$  samples with Ag dots.

The Royal Society of Chemistry apologises for these errors and any consequent inconvenience to authors and readers.

